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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/620,608	07/17/2003	Dong Kyun Sohn	0763-0173P 9674		
2292	7590 03/03/2004		EXAMINER		
	EWART KOLASCH &	PHAM, LONG			
PO BOX 74' FALLS CHU	/ JRCH, VA 22040-074	ART UNIT	PAPER NUMBER		
	,		2814		
			DATE MAILED: 03/03/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application	n No.	Applicant(s)				
Office Action Summary		10/620,60	8	SOHN ET AL.				
		Examiner		Art Unit				
		Long Pha		2814	<u> </u>			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply								
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).  Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).								
Status								
1)	)☐ Responsive to communication(s) filed on							
2a) <u></u> ☐	This action is <b>FINAL</b> . 2b) This action is non-final.							
3)□	☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
	closed in accordance with the practice un	der <i>Ex parte Qu</i>	ayle, 1935 C.D. 11, 45	3 O.G. 213.				
Disposition of Claims								
4)⊠	4)⊠ Claim(s) <u>1-5</u> is/are pending in the application.							
	4a) Of the above claim(s) is/are withdrawn from consideration.							
5)□	5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1,3 and 4</u> is/are rejected.								
•	Claim(s) <u>2 and 5</u> is/are objected to.							
8)□	8) Claim(s) are subject to restriction and/or election requirement.							
Applicati	on Papers							
9) The specification is objected to by the Examiner.								
10) The drawing(s) filed on is/are: a) □ accepted or b) □ objected to by the Examiner.								
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).								
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.								
Priority under 35 U.S.C. § 119								
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No. 09/461,767.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage</li> </ul>								
application from the International Bureau (PCT Rule 17.2(a)).								
* See the attached detailed Office action for a list of the certified copies not received.								
Attachme-	t(c)							
Attachment(s)  1) Notice of References Cited (PTO-892)  4) Interview Summary (PTO-413)								
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)								
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  Paper No(s)/Mail Date  5) Notice of Informal Patent Application (PTO-152)  6) Other:								

Application/Control Number: 10/620,608 Page 2

Art Unit: 2814

#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:
 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

2. Claims 1 and 4 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claims 1 and 4, it is unclear what process or material would constitute or produce a ternary phase layer.

# Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claim 3 is rejected under 35 U.S.C. 103(a) as being unpatentable over the applicant's admitted prior art (AAPA) of this application in view of Hirade (US '868).

With respect to claim 3, AAPA teaches a semiconductor device, comprising: a semiconductor substrate 11, fig.1a;

an insulation film 12 formed on said substrate to define a contact hole such that said substrate is exposed, fig. 1a;

a silicide layer 17 formed on said substrate and in said contact hole, fig. 1c;

Application/Control Number: 10/620,608 Page 3

Art Unit: 2814

a conductive plug on said silicide layer in said contact hole, fig. 1c; and a conducting layer 19 on said conductive plug, fig. 1e.

AAPA fails to teach that a diffusion prevention or barrier layer is located between the silicide layer and the conductive plug.

Hirade teaches that the formation of a diffusion prevention or barrier layer between a metal contact and a silicide layer results in a low resistance contact. See col. 2, lines 45-53.

It would have been obvious to one of <u>ordinary skill</u> in the art of making semiconductor devices to form a diffusion prevention or barrier layer between the silicide layer and the conductive plug in device of the AAPA to obtain the above advantage.

### Allowable Subject Matter

5. Claims 2 and 5 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Long Pham whose telephone number is 703-308-1092. The examiner can normally be reached on M-F, 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on 703-308-4918. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Application/Control Number: 10/620,608 Page 4

Art Unit: 2814

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

teng Phaper

Primary Examiner

Art Unit 2814